[ThE2] Next-Generation Slurries and Pad Technologies	
Session Date	November 13 (Thu.), 2025
Session Time	10:50-12:00
Session Room	Room E (Sicily Room, 1F)
Session Chair	Prof. Seho Sun (Yeungnam Univ., Korea)

[ThE2-1] **10:50-11:10**

Synthesis Strategies of Ceria Abrasives for Optimizing Dielectric Chemical Mechanical Planarization Performance

Jae Uk Hur and Jeong Ho Lee (Soulbrain Co., Ltd., Korea)

[ThE2-2] [Invited] **11:10-11:40**

New Pad for High Rate and Longer Life in W Bulk CMP

Ja-Eung Koo, Jung-Jik Cho, Chang-Il Kim, NanRong Chiou, and Dave Hui (DuPont, USA)

[ThE2-3] **11:40-12:00**

Development of ITO Stop Ag Slurry Based on Structural Differences in Carboxylic Acids

Junhyuk Kim and Jeongho Lee (Soulbrain Co., Ltd., Korea)